

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT:	Kurt, R.	Attn. Doc. No.: NL 021426 US1
SERIAL NO.:	10/539, 362	EXAMINER: Mulvaney, E. E.
FILED:	June 15, 2005	ART UNIT: 1794
		CONFIRMATION No.: 7350

***FOR: USE OF bi-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW
MATERIAL FOR OPTICAL STORAGE***

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

In response to the Office Action dated August 17, 2009, the Applicant hereby submits this paper within three (3) months (until **November 17, 2009**) of the mailing date of the Office Action, and requests amendment of the above-identified application as follows wherein:

Amendments made to the Claims begin on page 2, and
Remarks begin on page 11.